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Evaluation of the Radiation Susceptibility of a 3D NAND Flash Memory

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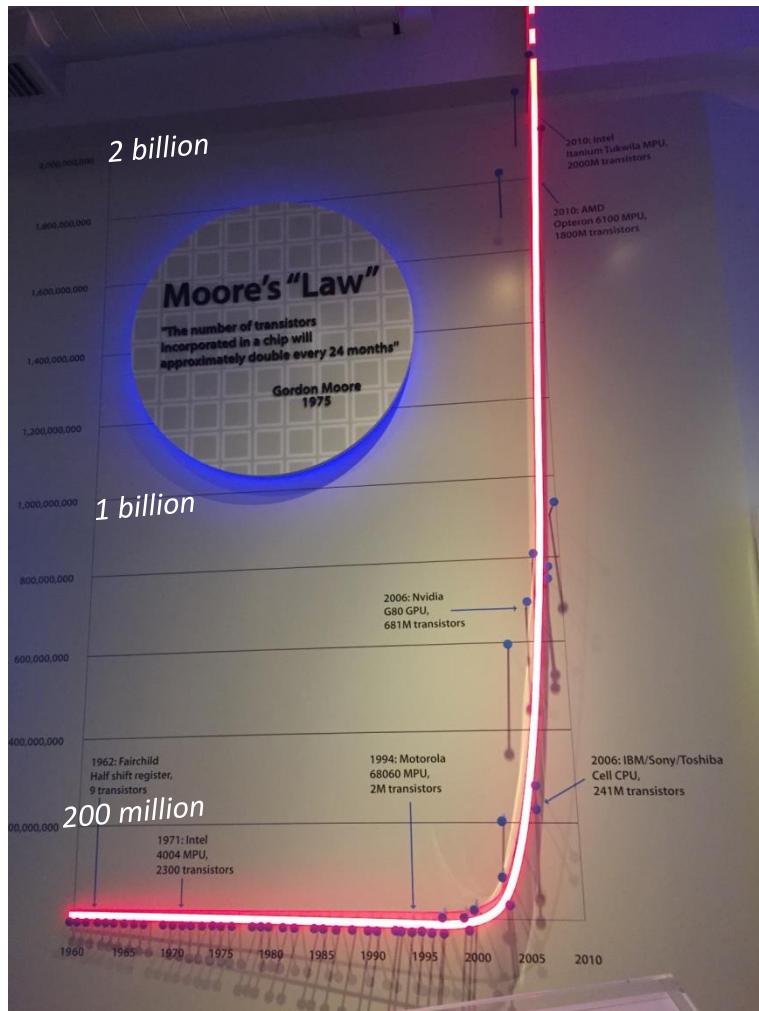
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3. NASA GSFC, Code 561, Greenbelt, MD 20771



Acronyms

- three dimensional (3D)
- multiple-bit upset (MBU)
- Massachusetts General Hospital (MGH)
- multiple-level-cell (MLC)
- negated AND or NOT AND (NAND)
- single-event functional interrupt (SEFI)
- single-event upset (SEU)
- silicon (Si)
- single-level-cell (SLC)
- total ionizing dose (TID)

MOTIVATION



- Samsung introduced the V-NAND in 2013 as planar flash has reached design limits [1]
- In Q3 2017, 3D NAND flash will exceed 50% of total NAND market for the first time [2]
- Samsung, Toshiba, Micron, and China's new entrant Yangtze River Storage plan to release 64-layer, and Hynix developing a 72-layer 3D NAND flash late 2017 to early 2018
- NASA, ESA and other parties in the space industry have implemented state-of-the-art NAND flash into flight missions [3], [4]
- Impact on single-event upset (SEU) including multiple-bit upset (MBU) sensitivity? Other mechanisms?

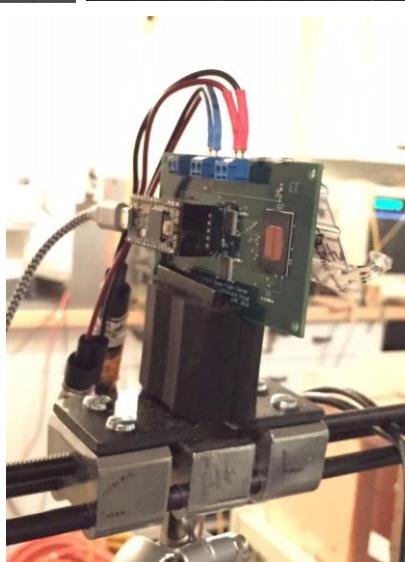
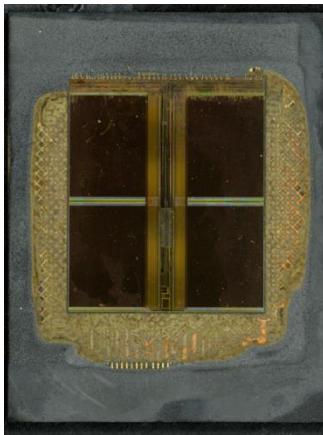
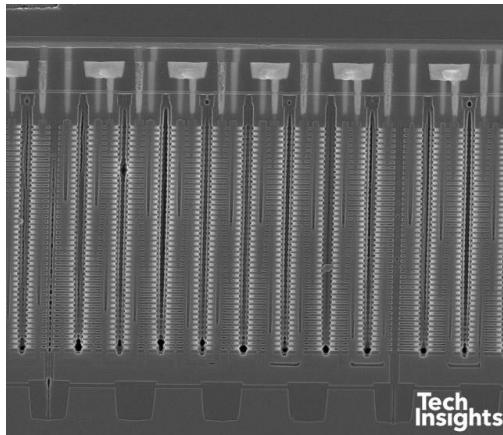
1. Samsung Electronics, "Samsung 3bit V-NAND memory boasts higher density to enhance capacity" Samsung Electronics Co., Ltd, South Korea, August, 2015.

2. <https://www.electronicsweekly.com/news/business/3d-nand-becomes-dominant-flash-memory-q3-2017-04/>

3. T. R. Oldham et al., "TID and SEE response of advanced Samsung and Micron 4G NAND flash memories for the NASA MMS mission," *IEEE Radiation Effects Data Workshop*, pp. 114–122, Jul., 2009.

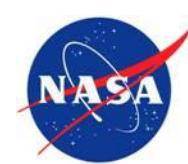
4. M. Fabiano and G. Furano, "NAND flash storage technology for mission-critical space applications," *IEEE Aerospace and Electronic Systems Magazine*, vol. 28, no. 9, pp. 30–36, Oct. 2013.

DEVICE AND EXPERIMENTAL

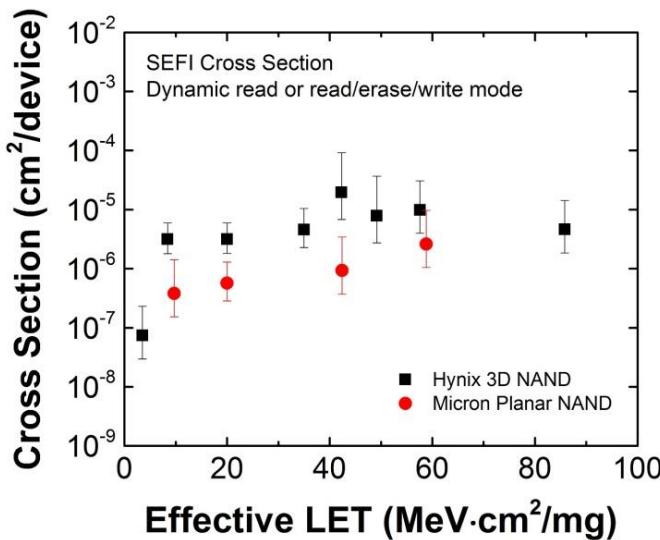


- Device under test
 - Hynix 128 Gb single die (40 nm) 3D NAND with gate-all-around charge-trap flash [1]
 - Micron 128 Gb single die (16 nm) planar NAND
- ARM Cortex-M4 Microcontroller and custom PCB mounted with flash
- Test Facility
 - Heavy ion testing at Lawrence Berkeley National Laboratory and Texas A&M University
 - High energy proton testing at Massachusetts General Hospital (MGH)
- Test modes
 - Static, dynamic read, dynamic read/read/erase/write
 - Patterns: All 0's, 1's (FF), checkerboard (AA and 55)

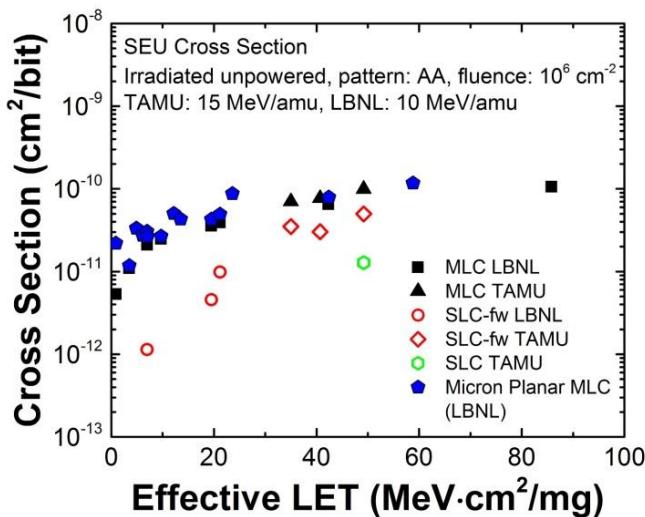
1. J. Choe. (2016). *SK Hynix in the Marketplace*. [Online]. Available: <http://www2.techinsights.com/about-techinsights/articles/SK-hynix-3D-NAND-in-the-marketplace>



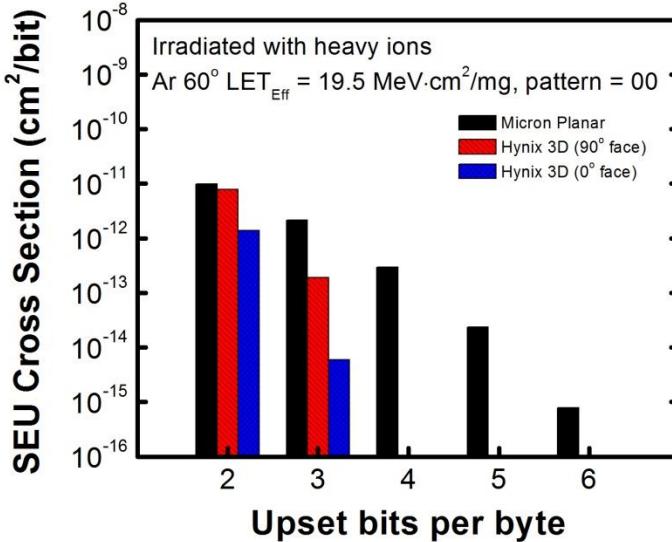
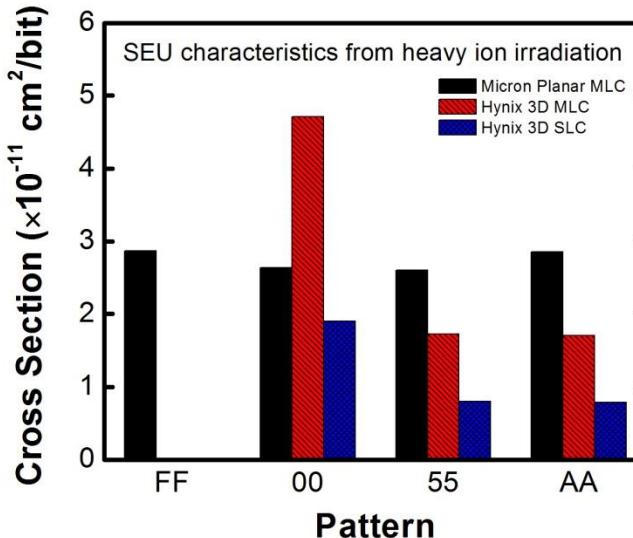
SEFI AND SEU CROSS SECTIONS



- Single-event functional interrupt (SEFI) observed during static on and dynamic tests
 - Power cycle can recover in most cases
- SEU cross sections similar to the Micron planar NAND in multiple-level-cell (MLC) storage mode
- Single-level-cell (SLC) mode produced significantly lower SEU cross sections
 - Plain SLC mode showed the least SEU susceptibility

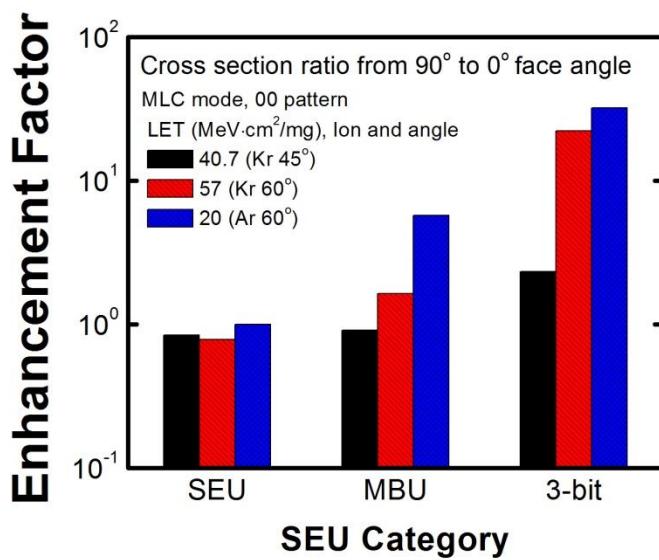
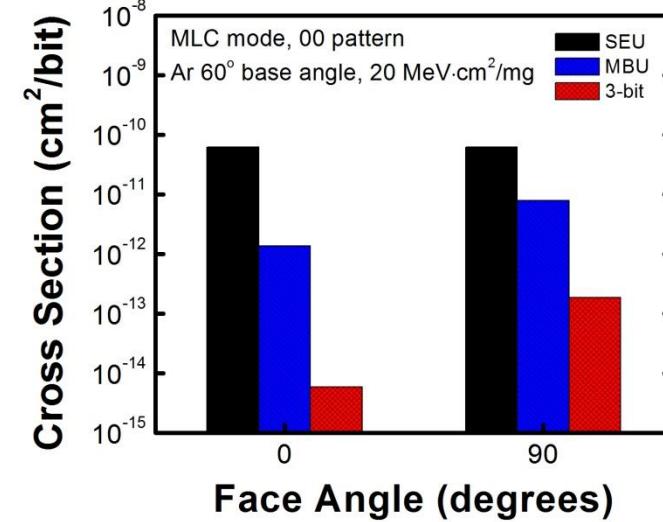
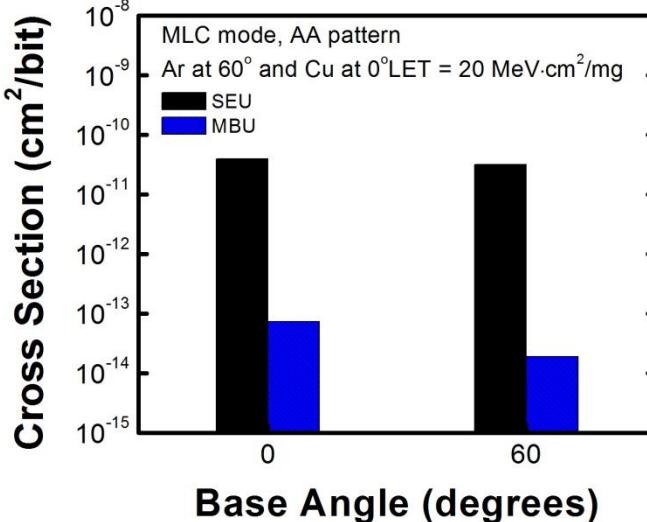


PATTERN DEPENDENCE



- Unique pattern dependence relative to the Micron planar NAND reflects different threshold voltage distribution schemes between the technologies
- Significant enhancement in SEU cross section for all 0's relative to checkerboard
- 3D NAND showed lower sensitivity to MBU relative to the planar NAND
 - Higher noise margin between program levels
- Enhanced MBU sensitivity at 90° to 0° face angle

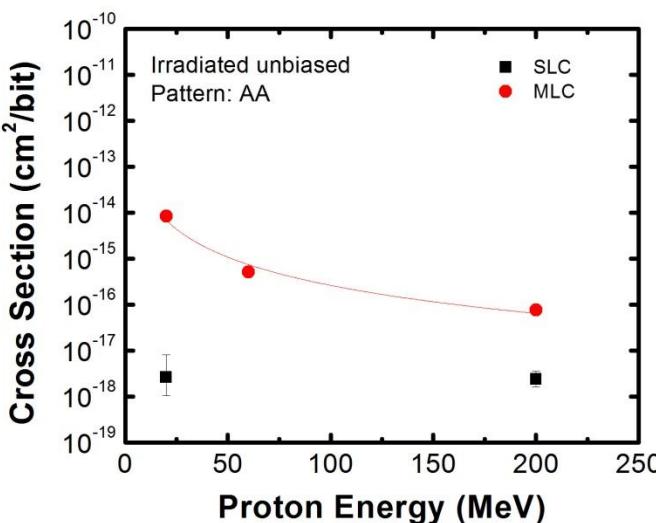
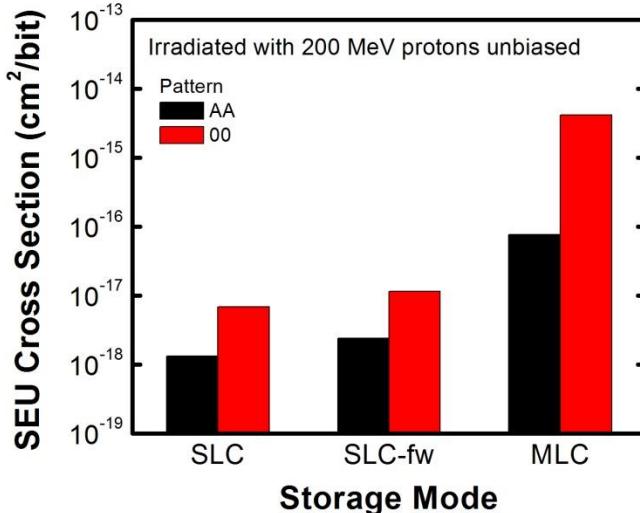
ANGULAR EFFECTS



- Cross section decreased slightly from normal incidence to 60° base angle for the same LET
- MBU cross section showed enhancement from 0° to 90° face angle
- Enhancement from 90° to 0° face angle more significant with increasing number of upset bits per byte
- Enhancement from 90° to 0° face angle more significant for higher base angle (60° vs. 45°)



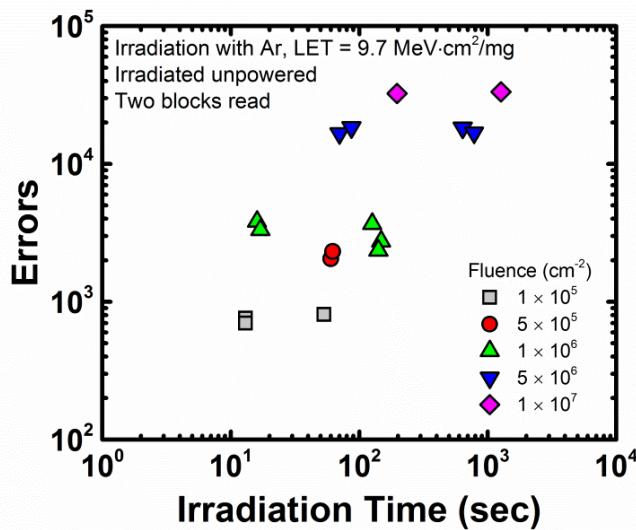
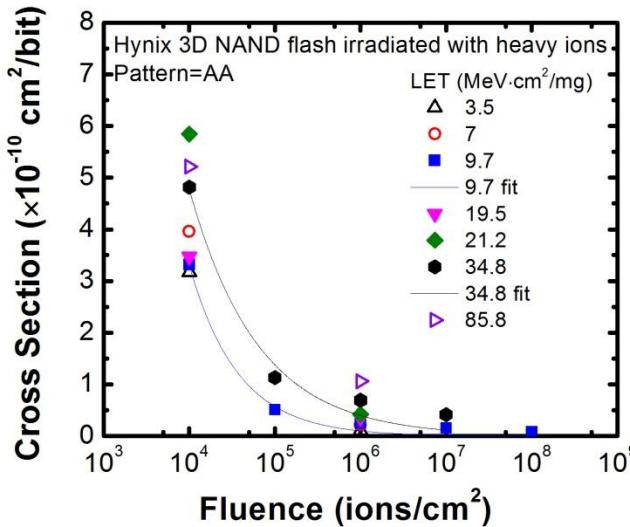
PROTON IRRADIATION



- SEU sensitivity to protons is significantly lower than heavy ions
- Similar pattern dependence and mode sensitivity
- Cross section increased for decreasing proton energy, similar to 41 nm Micron planar NAND flash [1]
 - Increase in the number of proton-induced secondaries with low LET
 - SEU LET threshold for MLC $< 0.9 \text{ MeV}\cdot\text{cm}^2/\text{mg}$, while for SLC is between 3.5 and 7 $\text{MeV}\cdot\text{cm}^2/\text{mg}$

1. M. Bagatin et al., "Proton-induced upsets in SLC and MLC NAND flash memories," *IEEE Trans. Nucl. Sci.*, vol. 60, no. 6, pp. 4130 – 4135, Dec. 2013.

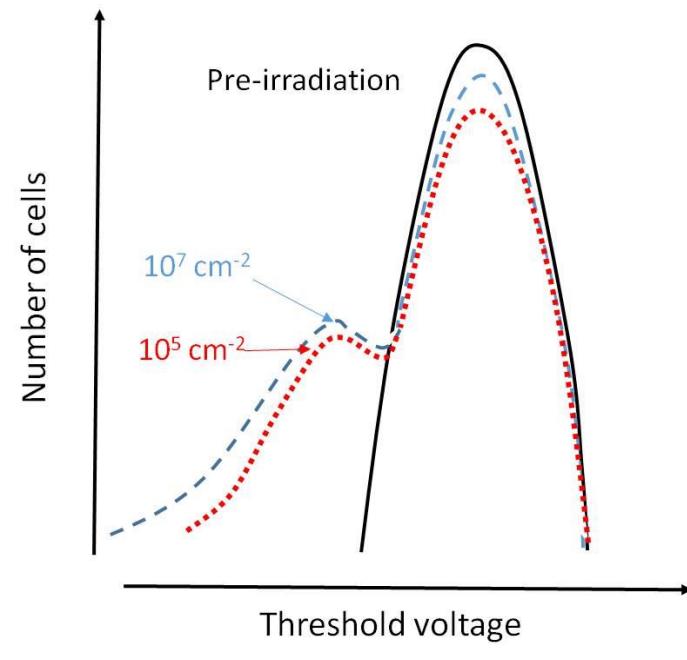
FLUENCE DEPENDENCE



- Cross section decreased for increasing fluence, similar to that observed for the 128 Gb Micron planar flash [1]
- Influence of dose on SEUs?
 - 1 krad(Si) or less for each run
- Annealing of SEUs?
 - Annealing on orders of hours [2]
- Irradiation runs with different durations, but the same fluence, resulted in similar cross sections
- ***Annealing and TID had negligible impact***

1. D. Chen et al., "Heavy ion irradiation fluence dependence for single-event upsets in a NAND flash memory," *IEEE Trans. Nucl. Sci.*, vol. 64, no. 1, pp. 332–337, Oct. 2016.
2. Bagatin et al., "Annealing of heavy-ion induced floating gate errors: LET and feature size dependence," *IEEE Trans. Nucl. Sci.*, vol. 57, No. 4, pp. 1835–1841, Aug. 2010.

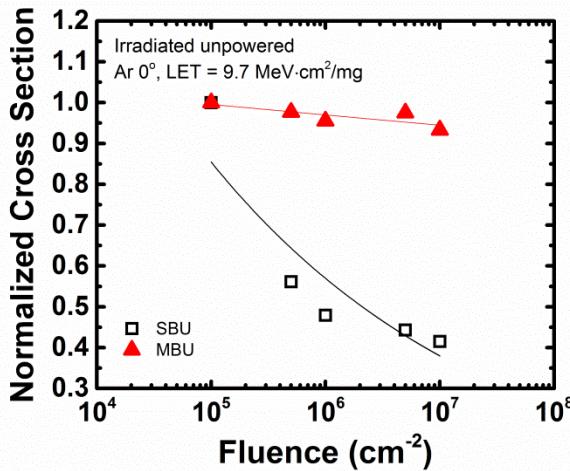
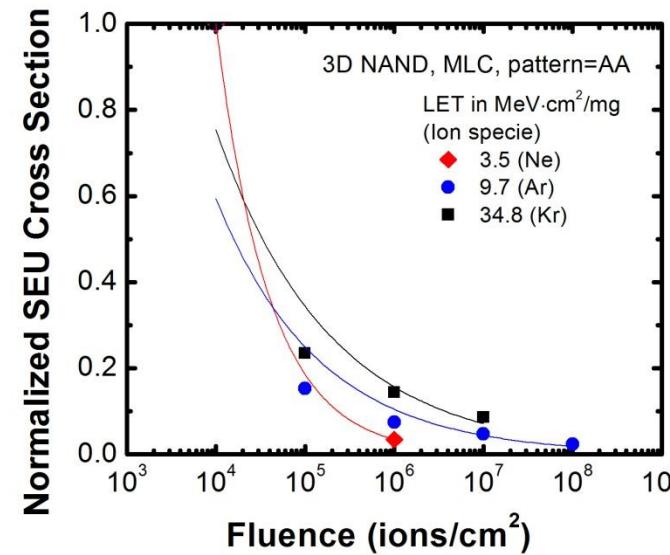
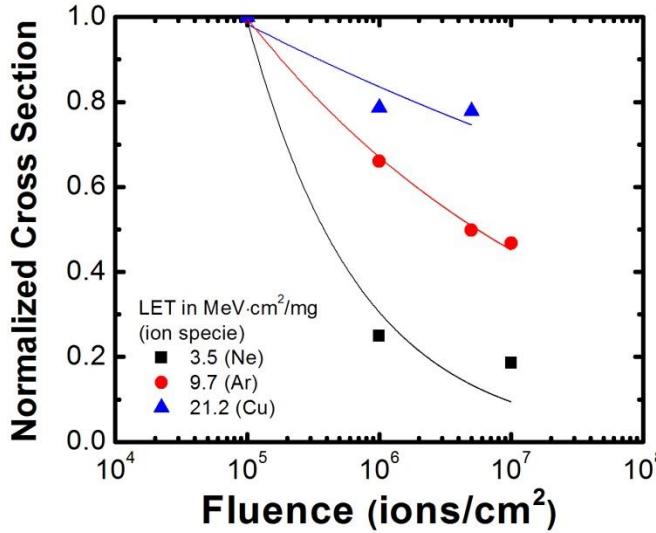
FLUENCE DEPENDENCE



- Attribute to the variable threshold voltage distribution of high density NAND flash
- High density results in poor coverage at typical irradiation fluence levels
- Cells with lower threshold voltages will be vulnerable to upset, while the majority of the population with higher threshold voltages are not susceptible to SEU
- We increasingly encounter a proportionally higher population of robust cells at a higher fluence than at a lower fluence, leading to the decrease in cross section with increasing fluence

1. G. Cellere, et al., "Anomalous charge loss from floating-gate memory cells due to heavy ions irradiation," *IEEE Trans. Nucl. Sci.*, vol. 49, No. 6, pp. 3051–3058, Dec. 2002.
2. S. Gerardin, et al., "Heavy-ion induced threshold voltage tails in floating gate arrays," *IEEE Trans. Nucl. Sci.*, vol. 57, no. 6, pp. 3199–3205, Dec. 2010.

FLUENCE DEPENDENCE



- Fluence effect more significant for lower LET ions
- Higher LET ions can upset a larger population with higher threshold voltages
- Fluence effect much more significant for single-bit upset than for MBU



CONCLUSION

- The more relaxed noise margins of 3D NAND leads to benefits in the SEU performance relative to planar NAND of similar performance and density
- Lower MBU sensitivity with less upset bits per byte
- Evaluation of MBU susceptibility requires irradiation at base and face angle orientations
- SEU cross section varied inversely with fluence, indicative of a variable SEU rate during mission
- Relatively robust against proton-induced SEE, characteristic of response of traditional planar NAND